

WEST

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140 and 16	0

Database:

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 IBM Technical Disclosure Bulletins

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USPT	129 and 131	46	<u>L39</u>
USPT	136 and 137	28	<u>L38</u>
USPT	copper or "Cu"	260583	<u>L37</u>
USPT	134 and 135	30	<u>L36</u>
USPT	((438/\$)!.CCLS.)	41876	<u>L35</u>
USPT	133 and 122	45	<u>L34</u>
USPT	129 and 132	47	<u>L33</u>
USPT	131 or 120	5381	<u>L32</u>
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USPT	129 and 120	1	<u>L30</u>
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USPT	127 and 117	89	<u>L28</u>
USPT	126 and 115	220	<u>L27</u>
USPT	125 and 111	807	<u>L26</u>
USPT	124 and 110	1120	<u>L25</u>
USPT	123 and 114	1460	<u>L24</u>
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USPT	112 near 8 121	8242	<u>L22</u>
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USPT	bottom adj antireflect\$4 adj coat\$3	31	<u>L19</u>
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USPT	112 near 8 116	1926	<u>L17</u>
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USPT	112 near 8 114	16632	<u>L15</u>
USPT	18 or 19	71161	<u>L14</u>
USPT	112 near 8 111	88671	<u>L13</u>
USPT	remov\$4 or etch\$4	1538586	<u>L12</u>
USPT	via or hole\$1	1273397	<u>L11</u>
USPT	pattern\$3 or photoresist	495120	<u>L10</u>
USPT	nitride or oxynitride	71127	<u>L9</u>
USPT	hardmask	230	<u>L8</u>
USPT	SiLK	19386	<u>L7</u>
USPT	14 same 15	134	<u>L6</u>
USPT	organic near 3 polymer	37160	<u>L5</u>
USPT	SILK	19386	<u>L4</u>
USPT	semiconduct\$4	231402	<u>L3</u>
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USPT	136 and 137	28	<u>L38</u>
USPT	copper or "Cu"	260583	<u>L37</u>
USPT	134 and 135	30	<u>L36</u>
USPT	((438/\$)!.CCLS.)	41876	<u>L35</u>
USPT	133 and 122	45	<u>L34</u>
USPT	129 and 132	47	<u>L33</u>
USPT	131 or 120	5381	<u>L32</u>
USPT	oxynitride	5205	<u>L31</u>
USPT	129 and 120	1	<u>L30</u>
USPT	128 and 121	59	<u>L29</u>
USPT	127 and 117	89	<u>L28</u>
USPT	126 and 115	220	<u>L27</u>
USPT	125 and 111	807	<u>L26</u>
USPT	124 and 110	1120	<u>L25</u>
USPT	123 and 114	1460	<u>L24</u>
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USPT	trench\$4	20669	<u>L21</u>
USPT	118 or 119	236	<u>L20</u>
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USPT	pattern\$3 or photoresist	495120	<u>L10</u>
USPT	nitride or oxynitride	71127	<u>L9</u>
USPT	hardmask	230	<u>L8</u>
USPT	SiLK	19386	<u>L7</u>
USPT	14 same 15	134	<u>L6</u>
USPT	organic near3 polymer	37160	<u>L5</u>

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USPT	semiconduct\$4	231402	<u>L3</u>
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USPT	KRAFT-ROBERT!	5	<u>L1</u>

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USPT	l17 abd l18	3668	<u>L19</u>
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USPT	intrametal near2 dielectric	3	<u>L12</u>
USPT	IMD	845	<u>L11</u>
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USPT	etch\$4 or remov\$	1486429	<u>L9</u>
USPT	l5 or l6 or l7	5381	<u>L8</u>
USPT	oxynitride	5205	<u>L7</u>
USPT	BARC	221	<u>L6</u>
USPT	bottom adj antireflective adj coat\$4	27	<u>L5</u>
USPT	pattern\$4 or etch\$4	539787	<u>L4</u>
USPT	trench\$3	20577	<u>L3</u>
USPT	via\$1	858202	<u>L2</u>
USPT	semiconduct\$4	231402	<u>L1</u>